

Electronic Supplementary Information for

Fabrication of hybrid membranes by incorporating acid-base pairs functionalized hollow mesoporous silica for enhanced proton conductivity

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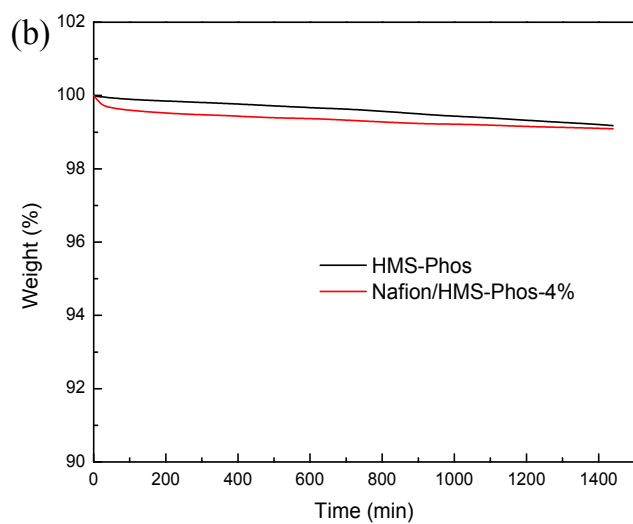
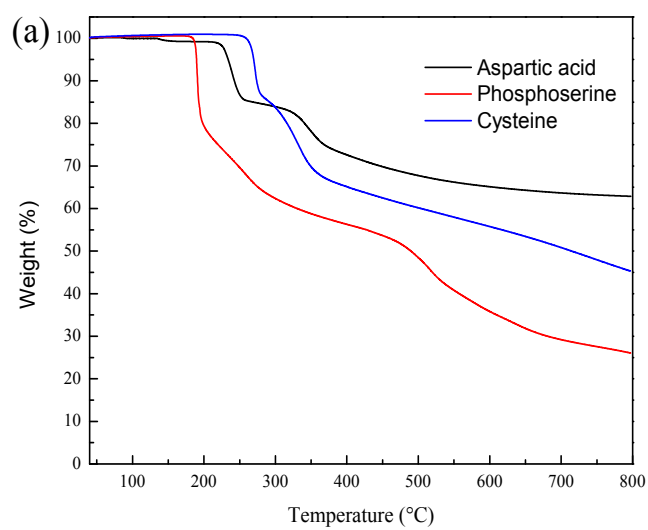


Fig. S1 TGA thermograms of (a) three kinds of amino acids; (b) HMS-Phos particles and Nafion/HMS-Phos-4% hybrid membrane.

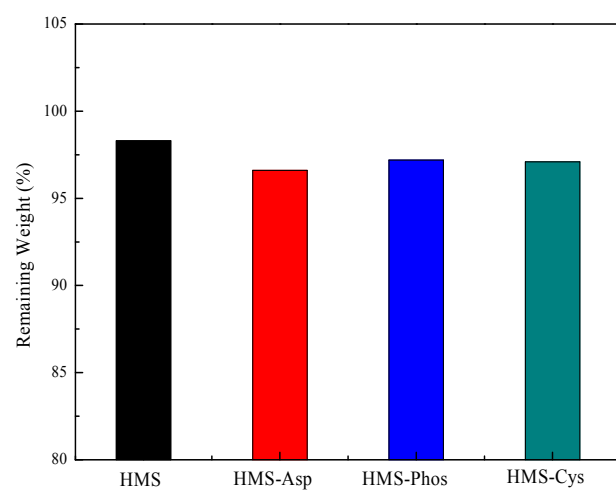


Fig. S2 The chemical stability of HMS and amino acid functionalized HMS under Fenton's test.

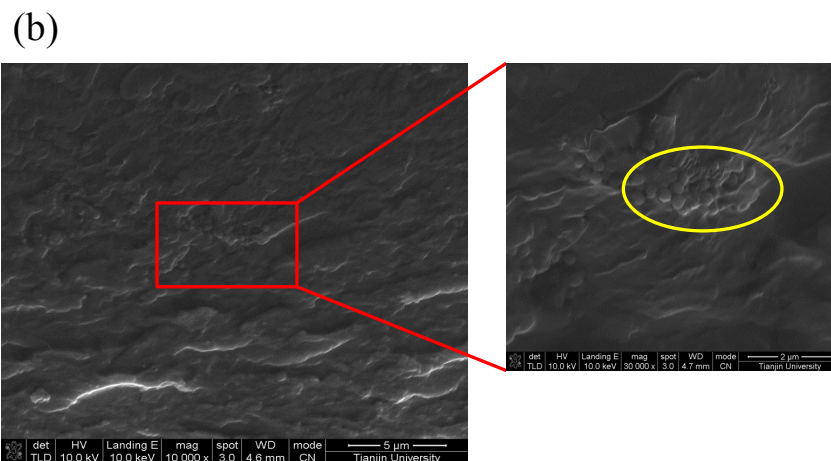
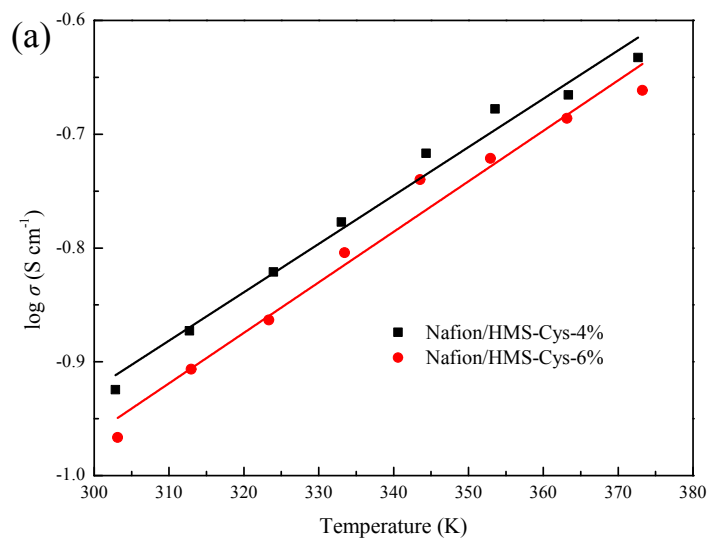


Fig. S3 (a) Proton conductivity of Nafion/HMS-Cys-4% and Nafion/HMS-Cys-6% hybrid membranes; (b) Cross-sectional SEM images of Nafion/HMS-Cys-6% hybrid membrane.

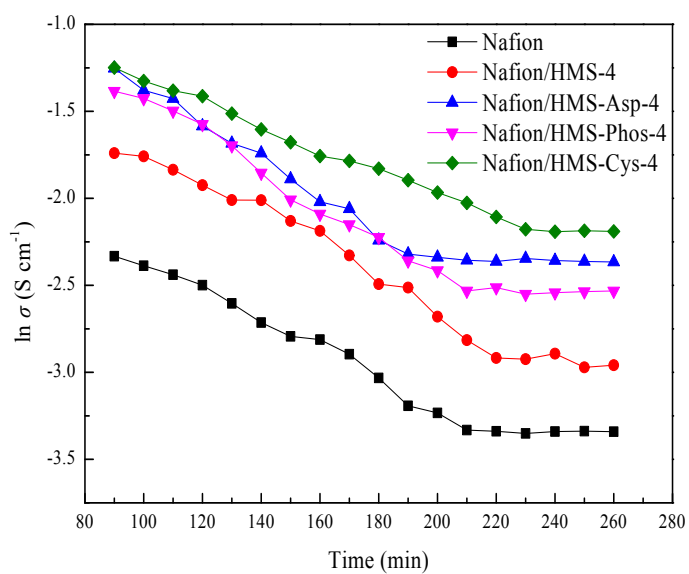


Fig. S4 Proton conductivity of hybrid membranes embedded with 4 wt% of HMS microspheres at 40°C and 20% RH after 90min.

Table S1 Typical proton conductivity of organic-inorganic hybrid membranes in literatures.

Membrane	Temperature (°C)	Relative Humidity (%)	Proton conductivity (S cm ⁻¹)	Reference
PEO/GO	25	100	0.086	S1
Nafion/ TiO ₂ -RSO ₃ H-10	40	100	0.036	S2
SiO ₂ -SO ₃ H/terpolymer/ poly(VDF-co-HFP)	25	100	0.021	S3
Nafion/S-ZrO ₂	80	50	0.04	S4
PVDF/CSPTC/TEOS/ +PEG-c	120	50	0.0206	S5
Nafion/Sulfopropylated Polysilsesquioxane	80	45	0.018	S6
Nafion/Sulfopropylated Polysilsesquioxane	120	45	0.022	S6
PFSA/sPOSS/PAA	120	50	0.107	S7
PFSA-aluminosilica	80	50	0.012	S8
PFSA-aluminosilica	120	50	0.026	S8
Nafion/F-GO	80	40	0.04	S9
Nafion/F-GO	120	40	0.09	S9
Nafion/phytic@MIL	80	40	0.018	S10
Nafion/PNT-5%	80	40	0.016	S11
Nafion/CS-SPION	80	50	0.06	S12
Nafion/S-Ph-PMO	60	40	0.0063	S13
SPES/silica	120	50	0.0018	S14
Nafion/HMS-Cys-4%	30	100	0.119	This work
Nafion/HMS-Cys-4%	80	51	0.027	This work
Nafion/HMS-Cys-4%	120	51	0.082	This work

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